



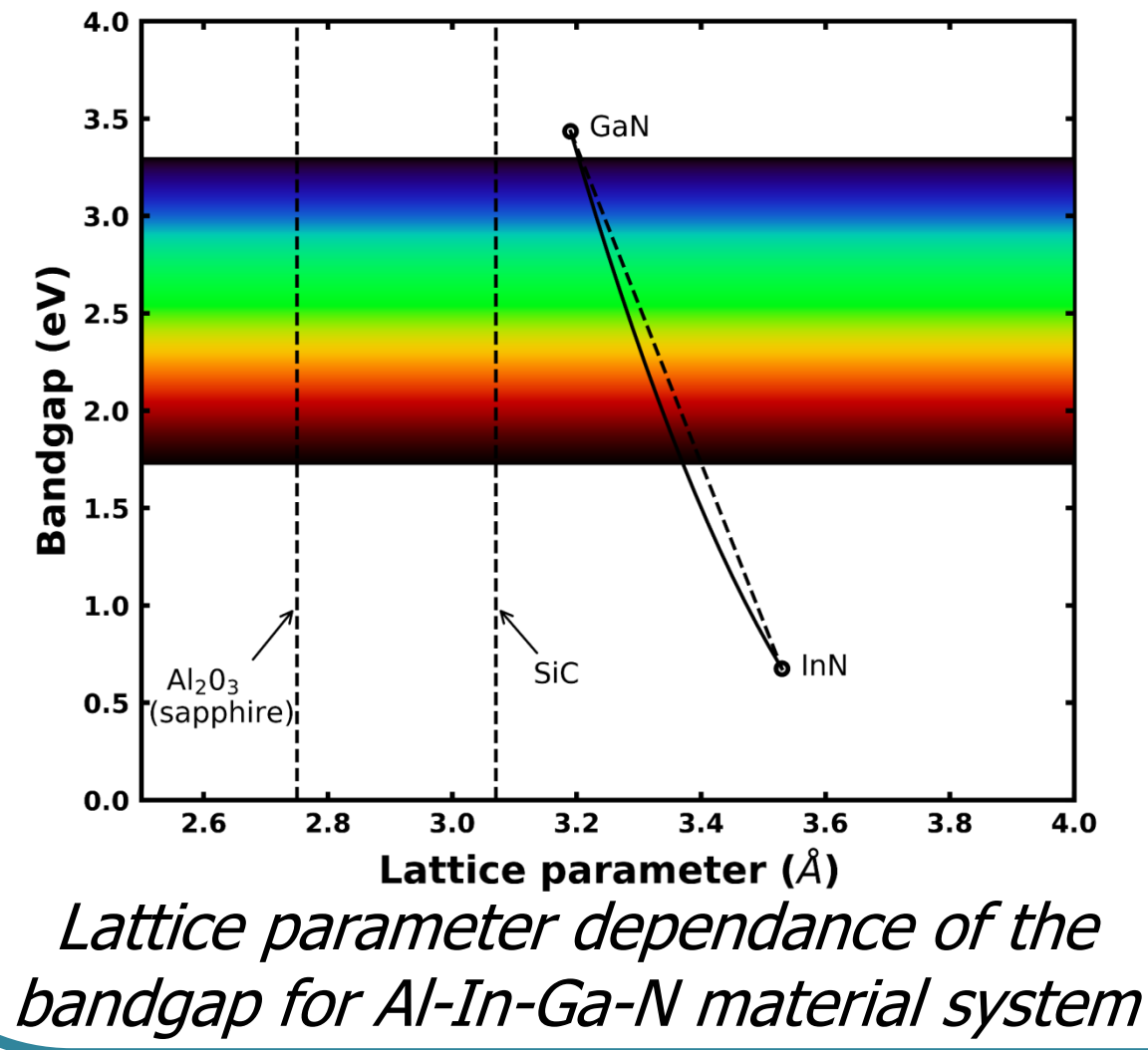
InGaN MBE growth of islands and thin film on epitaxial graphene

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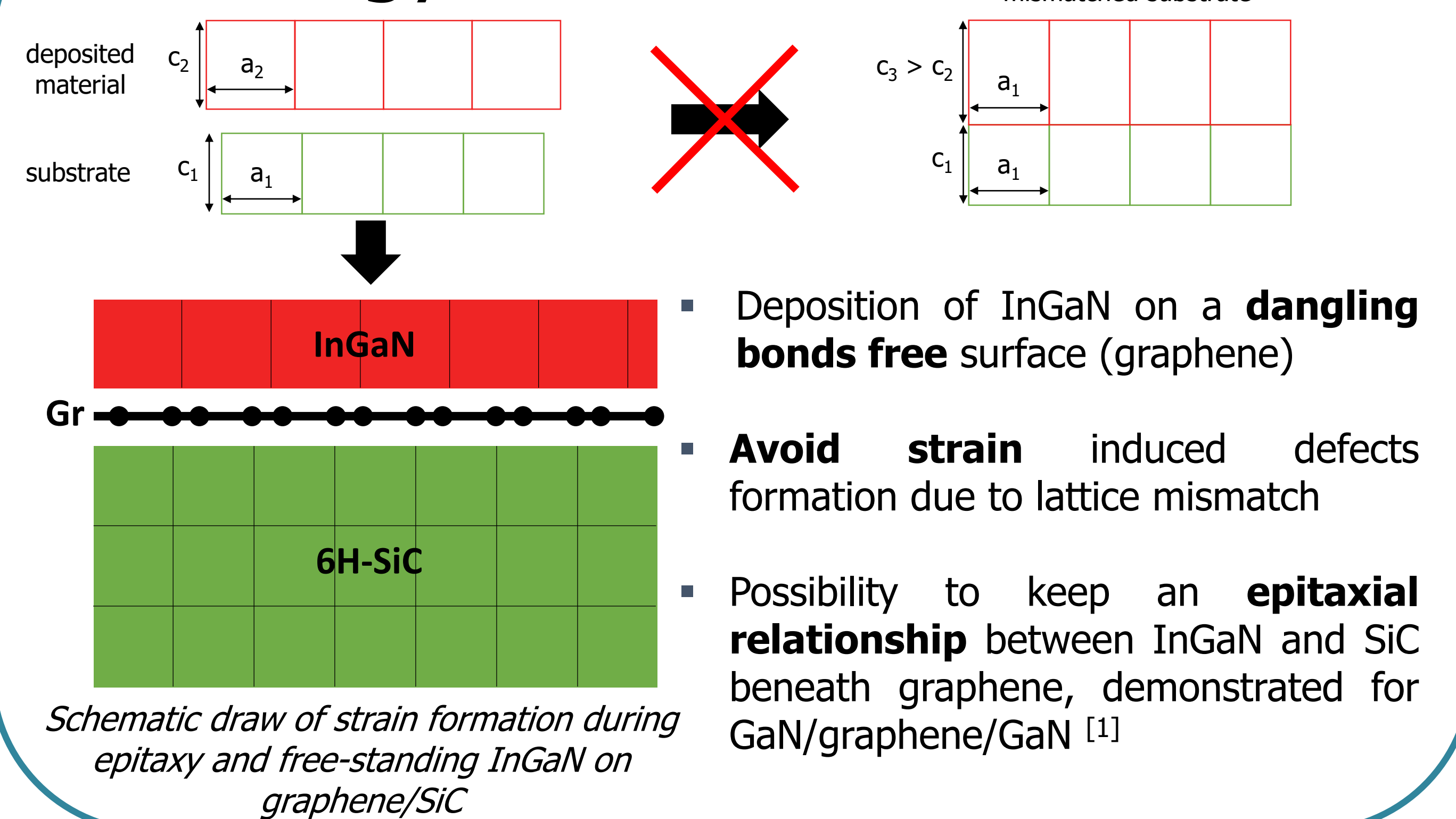
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Context



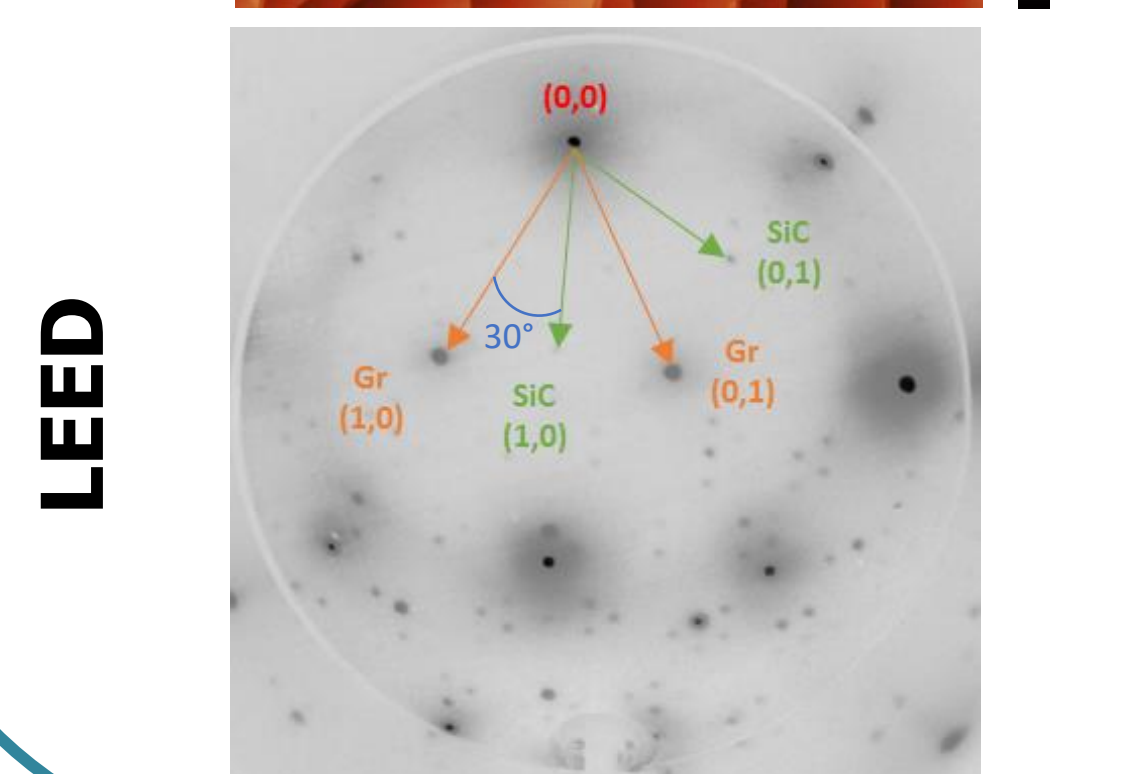
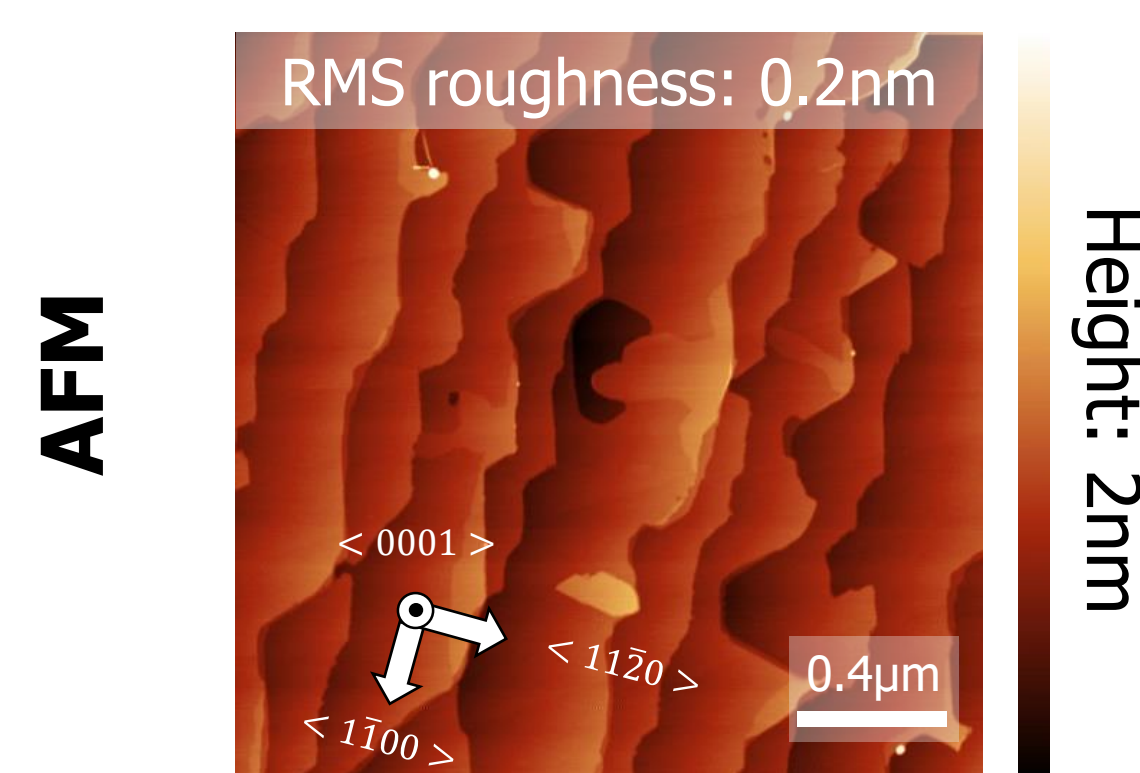
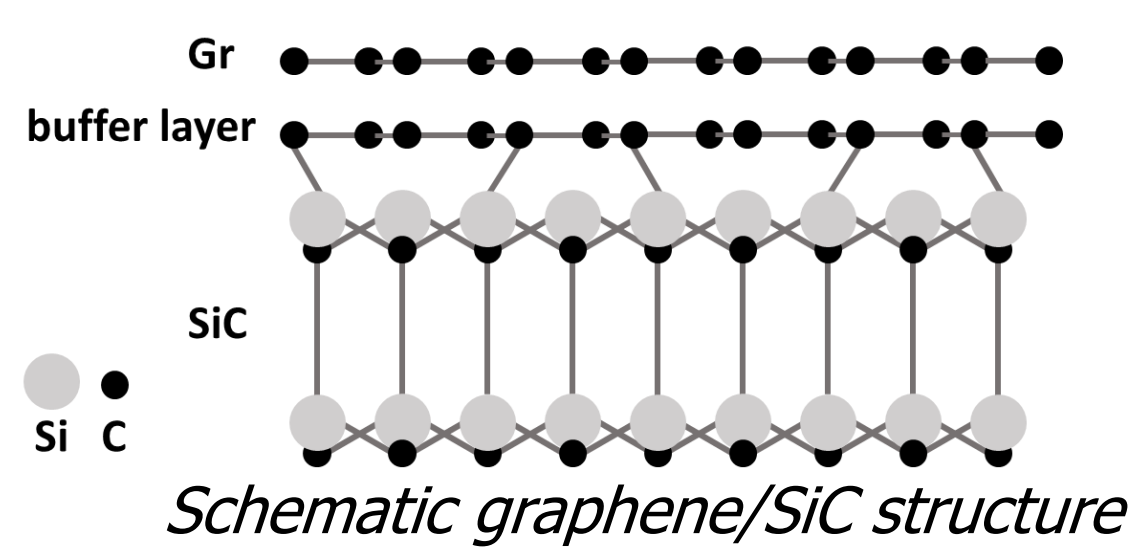
- In_{1-x}Ga_xN alloys for light emitting devices: possibility to cover the **whole visible range**
- Difficulty** to reach homogeneous **high In content** in InGaN alloys necessary for red LEDs (low miscibility, pulling effect)
- High **defects** density induced by **lattice mismatch** between InGaN and common substrates (GaN, Al₂O₃, SiC...)

Strategy

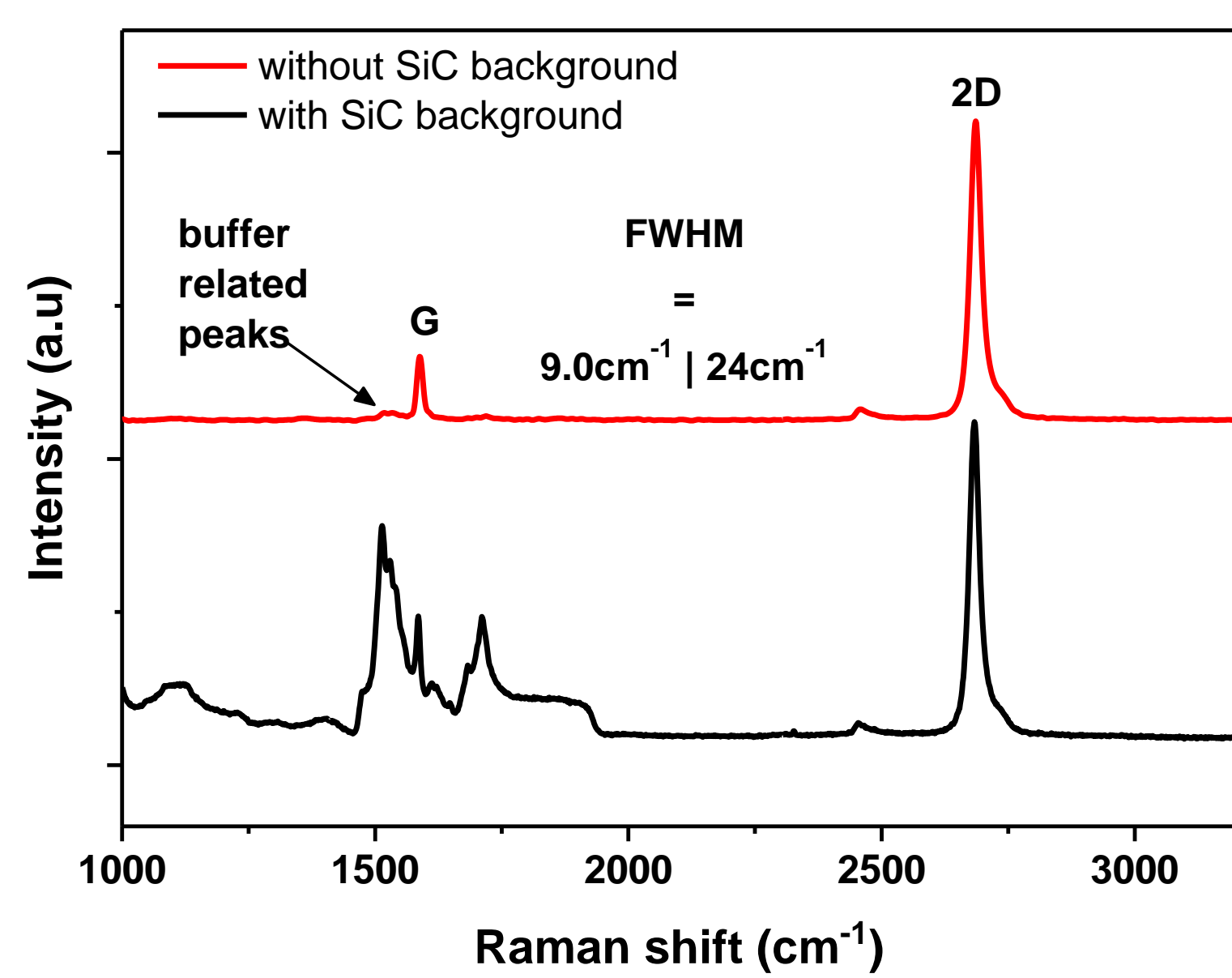


Growth of graphene on 6H-SiC (0001)

Propane based CVD growth at 1450°C under H₂/Ar atmosphere



Raman spectroscopy



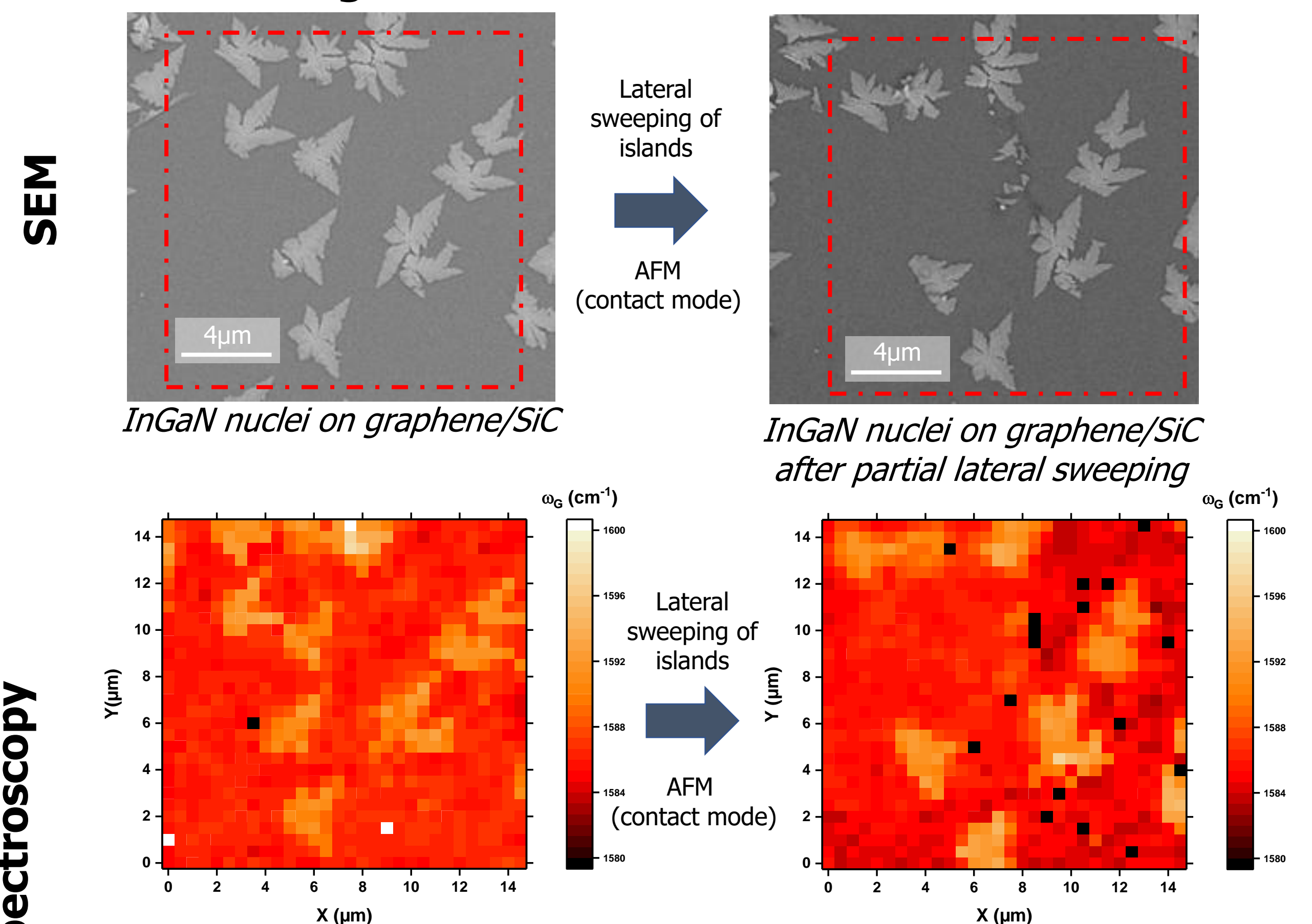
- Smooth surface of stepped SiC covered with graphene rotated by 30°
- High quality evidenced by Raman spectroscopy:
 - narrow 2D/G peaks FWHM
 - no D (defect related) peak around 1350 cm⁻¹

InGaN nucleation on graphene

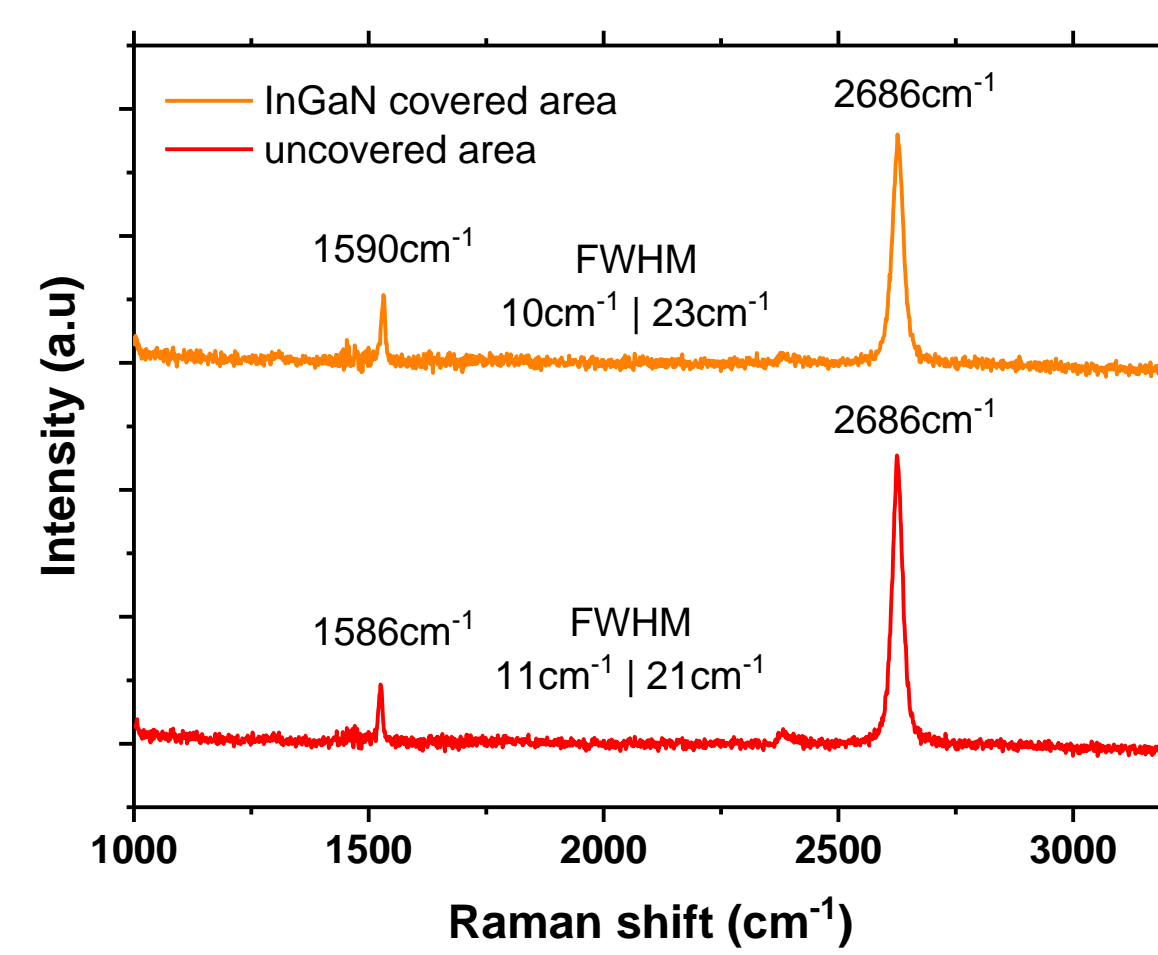
Ammonia assisted MBE at 685°C

C. Paillet et al., Nanotechnology, 31, 405601 (2020).

15min growth



Raman spectroscopy



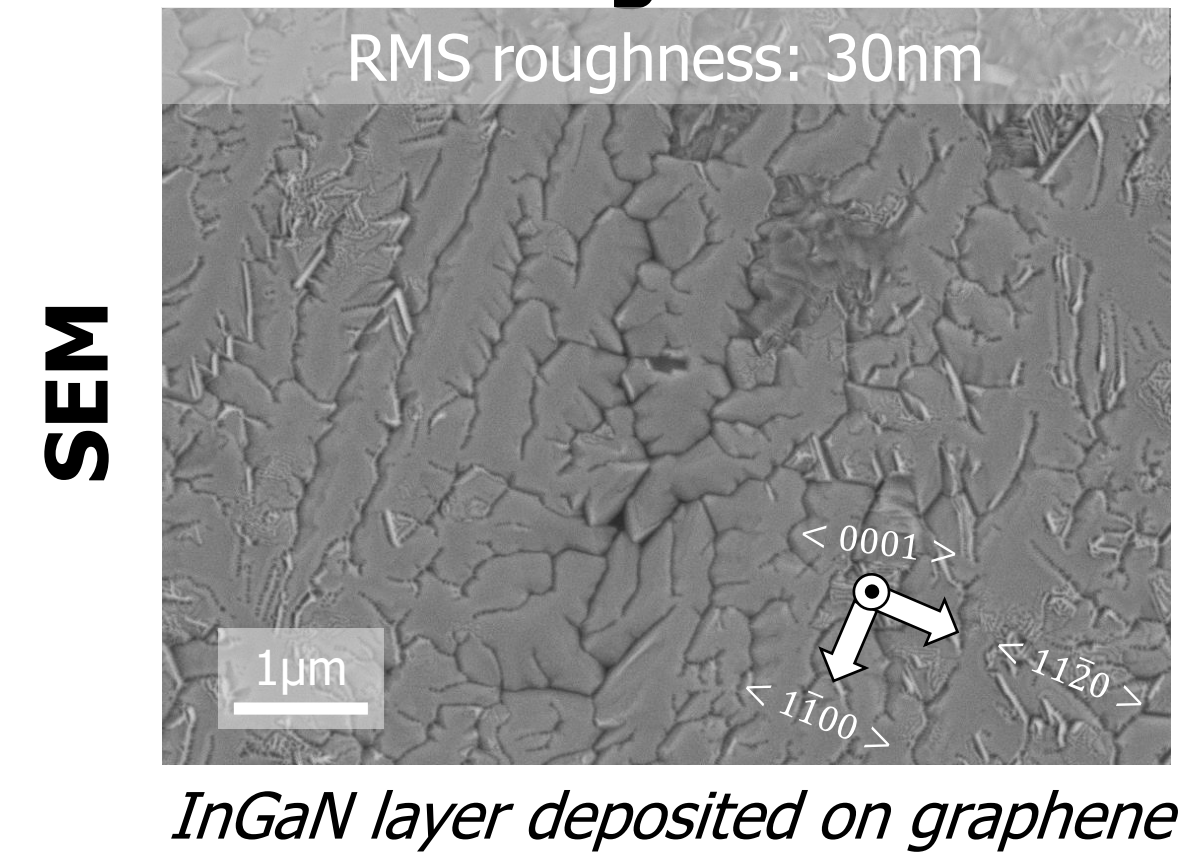
- Dendrite like nucleation:
 - density ≈ 5.5 × 10⁶ cm⁻²
 - height ≈ 25 - 40 nm
- No apparent damaging of the graphene probed by Raman spectroscopy:
 - No D peak after growth
 - G peak position shift by contact with InGaN (n-doping)^[2]
- Weak InGaN/graphene bonding** evidenced by AFM sweeping

Toward the formation of a film

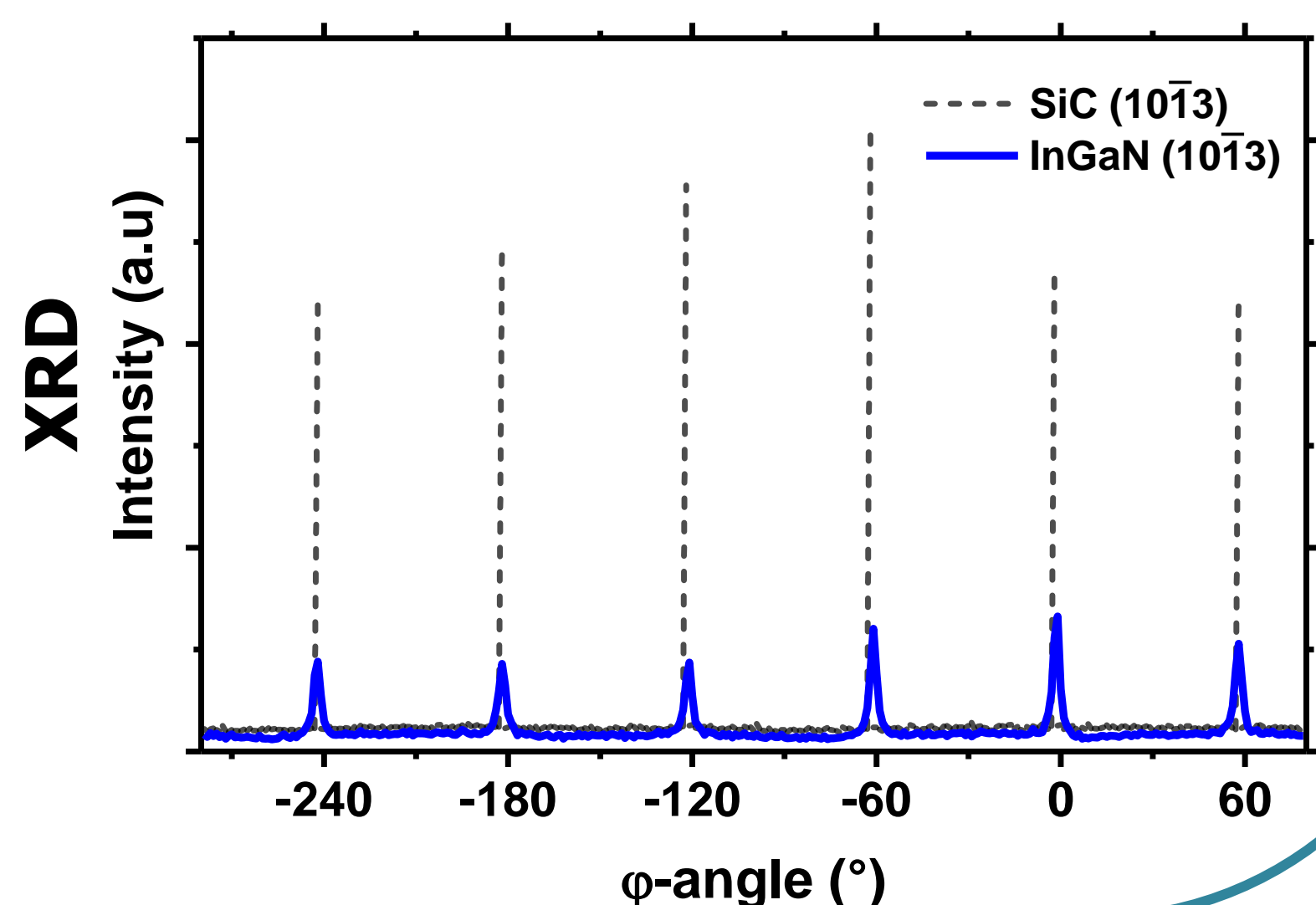
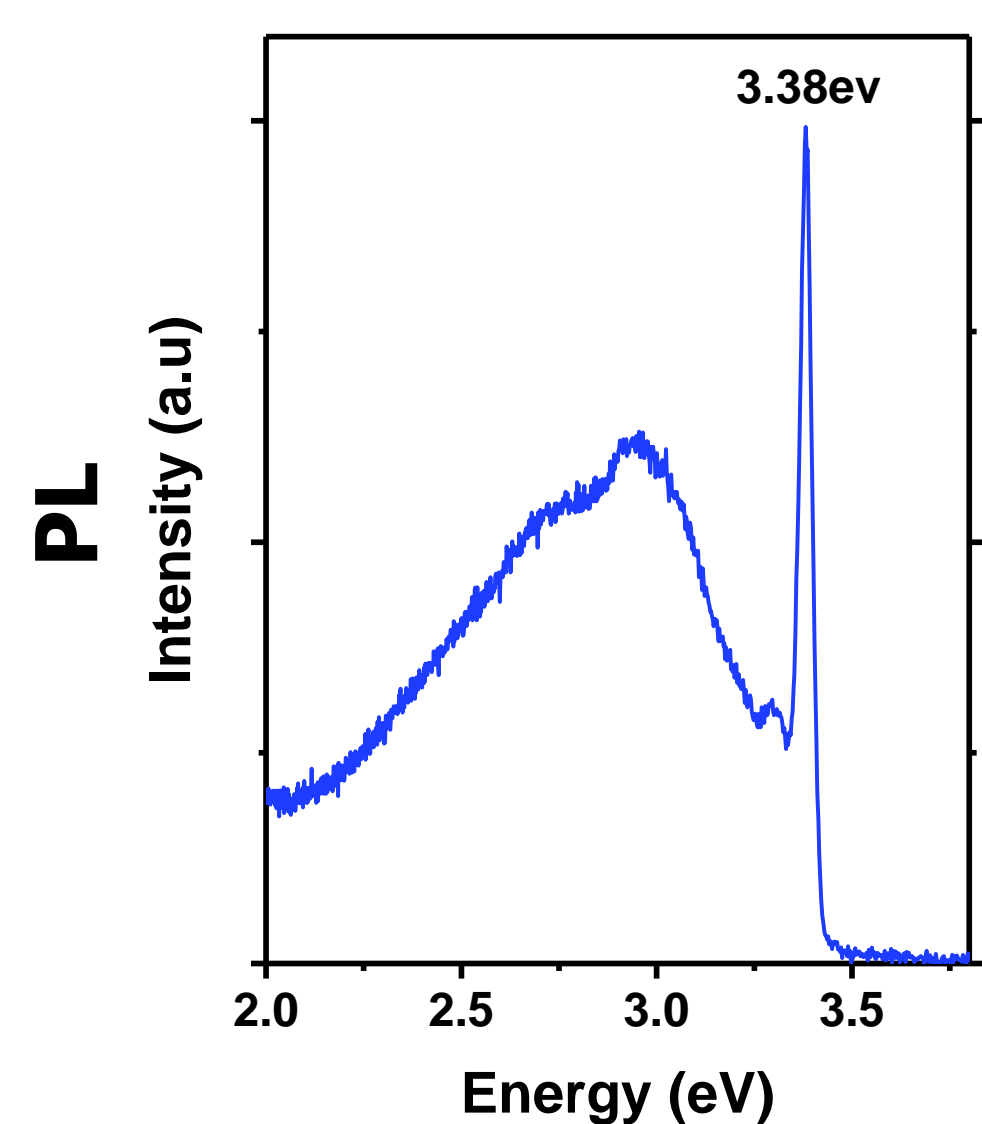
Ammonia assisted MBE at 615°C

C. Paillet et al., Nanotechnology, 31, 405601 (2020).

2hrs growth



- Non-fully coalesced InGaN film observed with SEM (thickness: 70 nm)
- Epitaxial relationship** between InGaN and SiC shown by φ-scan
- (0002) **rocking curve** FWHM = 515 arcsec:
 - commensurate with InGaN (6% at In) on InGaNOS (395 arcsec)^[3] and GaN on graphene/SiC (680 arcsec)^[4]
- Low In incorporation** (≈ 2% at) according to InGaN band edge PL emission wavelength



Summary

- Direct nucleation of weakly bonded InGaN islands on graphene without degradation
- High roughness InGaN film with low In incorporation in epitaxial relationship with SiC substrate
- Lower growth temperature tested to enhance In incorporation (up to ≈ 25% at In) resulting in a much lower material quality

Perspectives

- Improve the nucleation process
- Indentation tests to probe the InGaN/graphene interaction forces

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